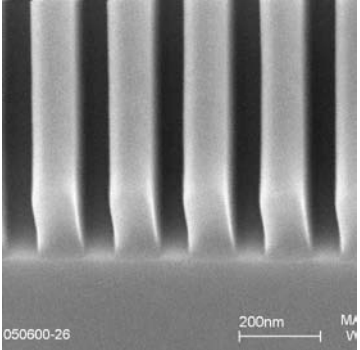


**Materials** Nanonex offers high performance materials in multiple series, optimized for nanoimprint processes based on experimental tests of thousands of material combinations. All resists are engineered and manufactured by Nanonex. Nanonex offers high quality periodic masks that are patterned edge to edge and available in various sizes and substrates to fit your needs.

**NXR-1000 Series Features**

**Thermal Nanoimprint (T-NIL) Resists**

- Fast response
- Excellent uniformity
- Ultra-high resolution
- Low imprint pressure
- Low imprint temperature
- Good flow ability
- Excellent adhesion
- Suitable for direct etch and lift-off processes
- Customized versions available for specific spin thickness

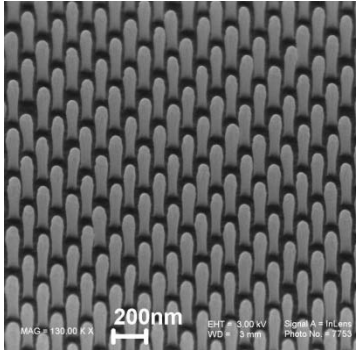


**NXR-1000**

**NXR-2000 Series Features**

**Photo-curable Nanoimprint (P-NIL) Resists**

- Super fast response
- Unmatched flow ability
- Outstanding uniformity
- Ultra-high resolution
- Low curing dosage / high UV-photo sensitivity
- Very low imprint pressure
- High plasma etch resistance
- Spin-on or resist-drop dispense
- Customized versions available for specific spin thickness

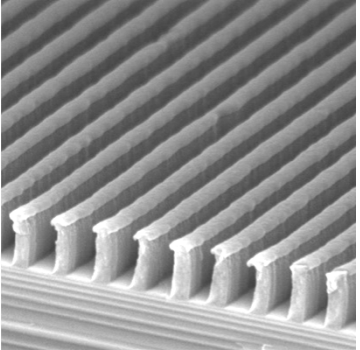


**NXR-2000**

**NXR-3000 Series Features**

**Underlayer Resists**

- Great versatility
- Superior etch resistance
- Enhanced properties to optimize lift-off and direct etch processes
- Compatible with top-layer
- Planarizing sample surfaces
- Can be removed with water or methanol, alternate version removed by acetone
- Customized versions available for specific spin thickness



**NXR-3000**

**NXT-110 Features**

**Nanoimprint Mask Release Treatment**

- Forms durable monolayer to allow easy release of mask from substrate
- Stable properties after treatment

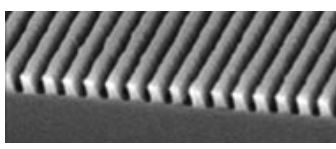
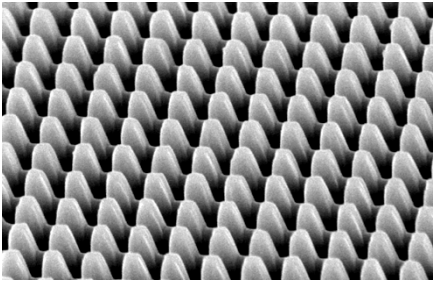


**NXT-110**

**Periodic Masks**

**Nanoimprint Masks**

- Masks of Periodic 1D or 2D patterns
- Custom Mask Services
- Assistance For Complex Masks

**Masks**

For more information visit us at <http://www.nanonex.com>